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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10047266	FILING DATE 01/14/2002	CLASS 438	SUBCLASS 706	GAU 2812	EXAMINER Chen, K
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**APPLICANTS: Ke Chih-Ming; Gau Tsai-Sheng; Shin Jaw-Jung; Yen Anthony;

**CONTINUING DATA VERIFIED:

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** FOREIGN APPLICATIONS VERIFIED:

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO 67,200-641
35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no		
Verified and Acknowledged Examiners's initials		
TITLE : Reducing photoresist shrinkage via plasma treatment		

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		Assistant Examiner	CLAIMS ALLOWED	
			Total Claims	Print Claim for O.G.
ISSUE FEE		Primary Examiner	DRAWING	
Amount Due	Date Paid		Sheets Drwg.	Figs. Drwg.
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	Application Examiner	
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